Ref #	Hits	Search Query	DBs	Default Operator	Piurals	Time Stamp
S1	1	10/658372	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/04/20 18:53
S45	936	204/192.11,192.27,192.28.ccls.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/04/21 10:04
S46	1056	148/518,525,537,668.ccls.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/04/21 10:05
S47	2944	427/527,531,532,534,535,160.ccls.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/04/21 10:05
S48	77	148/713.ccls.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/04/21 10:05
S49	7960	430/5.ccls.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/04/21 10:06
S50	3553	430/311.ccls.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/04/21 10:06
S51	193300	(mask or photomask or reticle).ti, ab,clm.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/04/21 10:08
S52	1054018	(blank or substrate).ti,ab,clm.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/04/21 10:08
S53 _.	420729	mask or photomask or reticle	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/04/21 10:08
S54	1595356	blank or substrate	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/04/21 10:09
S55	594156	reflective or reflection or reflecting	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/04/21 10:09
S56	201048	multilayer or multi layer	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/04/21 10:10
S57	8602	extreme ultraviolet or extreme ultra violet or extreme UV or EUV or soft xray or soft x ray	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/04/21 10:11

S58	3	(S45 or S46 or S47) and S51 with S52 with S55 with S56 and S57	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/04/21 10:13
S59	4	(S45 or S46 or S47) and S53 with S54 with S55 with S56 and S57 not S58	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/04/21 10:14
S60	2	(S45 or S46 or S47) and S53 same S54 same S55 same S56 and S57 not S58 not S59	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/04/21 10:15
S61	3189524	heat\$3 or bak\$3 or thermal\$2	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/04/21 10:17
S62	85063	(compress\$3 or tens\$3) with stress	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/04/21 10:18
S63	570956	stress	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/04/21 10:18
S64	1500895	mix or mixed or mixing or intermix or intermixed or intermixing	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/04/21 10:18
S65	. 490503	diffuse or diffusion or diffused or diffusing or interdiffuse or interdiffusion or interdiffused or interdiffusing	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/04/21 10:19
S66	1184680	S61 same (degree or "C" or "F")	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/04/21 10:21
S67	94999	(molybdenum or "Mo") same (silicon or "Si") or "Mo/Si"	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/04/21 16:38
S68	5483647	avoid\$3 or suppress\$3 or stop\$4 or prevent\$3 or inhibit\$3	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/04/21 10:25
S69	1618	S67 same (S61 or temperature) same (S62 or S63)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/04/21 10:44
S70	60	S67 same (S61 or temperature) same (S62 or S63) same S68 same (S64 or S65)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/04/21 10:31
S71	60	S70 not S58 not S59 not S60	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/04/21 10:47
S72	4433	(resist or photoresist) with amplif\$4	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/04/21 10:32

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S73	481	(electron beam or e beam) with S72	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/04/21 10:34
S74	55	S73 same S53 with S54	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/04/21 10:37
S75	7	S74 same S61 same (degree or "C" or "F")	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/04/21 16:09
S76	1	S48 and S67	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/04/21 17:40
S77	2	S70 same liquid	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/04/21 10:47
S78	8	S67 same S55 same S56 same S61 same (liquid or fluid or clean\$3 or acid)	US-PGPUB; USPAT; EPO; JPO	ADJ -	ON	2006/04/21 10:51
S79	58	(S49 or S50) and (S51 or S53) same S55 same S56 same S61	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/04/21 11:03
S80	28	S79 and S66	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/04/21 11:02
S81	1422	378/34-35.ccls.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/04/21 11:02
S82	139	S81 and (S51 or S53) same S55 same S56	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/04/21 11:05
S83	431165	resist or photoresist	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/04/21 11:05
S84	1077647	semiconductor or wafer	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/04/21 11:07
S85	93	S82 and S53 same S83 same S84	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/04/21 11:08
S86	20	S85 and S83 same S61	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/04/21 11:10
S87	18	(Tsutomu near2 Shoki).in. and (Hoya).as. not S58 not S59 not S60 not S71 not S75 not S76 not S77 not S78 not S80 not S86	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/04/21 11:16

S88	0	(Tsutomu near2 Shoki).in. not S58 not S59 not S60 not S71 not S75 not S76 not S77 not S78 not S80 not S86 not S87	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/04/21 11:16
S89	14	S74 same S61 not S75	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/04/21 16:38
S90	192041	anneal\$3	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/04/21 16:38
S91	61771	((molybdenum or "Mo") same silicon) or "Mo/Si"	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/04/21 16:39
S92	14850	S91 same (S61 or S90) not S58 not S59 not S60 not S71 not S75 not S76 not S77 not S78 not S80 not S86 not S87 not S89	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/04/21 16:42
S93	180	S92 and S55 with S56	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/04/21 16:43
S94	87	S92 same S55 with S56	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/04/21 16:43
S95	3310	134/3,28,41.ccls.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/04/21 17:41
S96	7	S95 and S91 same (S61 or S90)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/04/21 17:43